Tracking/Vertex Detector (I)

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Outline

- Introduction
- Silicon Detectors
 - Working Principle
 - Characteristics
 - Radiation Damages
- Design Consideration of Silicon Tracker
- Reconstruction in Tracking Detector

Tracking of Charged Particle

- Tracking : measurement of the charged particle trajectory (track) i.e the direction and magnitude of it's momentum
- How Tracking is done?
 - Charged particles leave trails in detector active layers due to its interaction with matter
 - Such trails are "reconstructed" as "Hits"
 - "Hits" are connected together (pattern recognition) to find the trajectory of charged particle (track)
 - Point from where tracks are originated, reconstructed as vertex
- Momentum of track is measured from its curvature in the magnetic field

What do we measure

Momentum in_magnetic field





At 2T magnetic field • $P_{\perp} = 1$ GeV R = 1.67m • $P_{\perp} = 10$ GeV R = 16.7cm

Assuming a track of length 1 m

•
$$P_{\perp} = 1 \text{GeV}$$
 s = 7.4 cm
• $P_{\perp} = 10 \text{ GeV}$ s = 0.74 cm

The sign of the charge from the bending in the magnetic field



Why Silicon in Tracking System (I)

High Energy Physics in mid 70's

- New quarks (c, b) and leptons (τ)
- Life time 10^{-13} s <= $c\tau$ <= 10^{-12} s



- Standard Tracking Detectors (wire chambers) resolution of 100-200 μm became less sensitive to measure such distances
- A new tracking device with of spatial resolution of 10-20µm became very important

Why Silicon Detector (II)

• The Idea : the array of silicon diodes can be used as tracking detector (1978-1980)



Silicon Microstrip Detector



- Gain : 10⁴
- Ionisation Energy : 30 eV
- Spatial Resolution : 100-200 μm
- Response Time : 100 ns

• Size :

Not compact

None (ionisation μ thickness) 3.6 eV 10-50 μm (density) 10-50 ns

Compact

Working Principle

- The device should be free of charge carriers for efficient signal collection
- Reversed bias p-n junction
 - Depletion at the junction extends in the bulk
 - Behaves like a resistor drawing no currents under applied voltage
- Depleted junction acts as detector for particle trajectory
 - Charge (e-h pair) created due to passage of charged particle and collected at the junction
- Very low ionisation energy (3.6eV) and large energy loss by minimum ionizing particles...
 - large (~24k) e-h pairs created in a 300 μ m silicon







The Layout

- p⁺ micro-strips on n-type silicon bulk
 - Bias voltage applied at the back side
 - Charge collected from p+ strips, electronics AC coupled
 - n+ implant at the back and at the cutting edge
- The pitch of the strips defines spatial resolution in ideal case



The Signal

- Ionization produced in the depleted region by minimum ionizing particles
- Large energy loss due to low ionization energy
 - Landau distribution
- Fluctuations due to knock on electro
 - $(dE/dx)_{most prob} = 0.26 \text{ KeV}/\mu m$
 - (E_{Loss})_{most-prob}~72 e-h pairs
 - <E_{loss} >_{mean} ~ 108 e-h pairs
 - 300µm thickness => 24K electrons
- Full depletion needed to collect the created charge efficiently



The Noise

Possible sources

- Leakage current : drift of thermally generated minority carriers
 - $I_{leak} = 0.5 \text{ q W } (n/\tau_0)$ [W depletion depth, τ_0 life time of charges]
 - No direct temperature term but enters through charge density n
- Capacitive coupling to the electronics

 $ENC = A + B C_{tot}$ $C_{tot} = C_{bulk} + 2 (C_{1n} + C_{2n} +)$

- Ctot μ strip width/strip pitch
- Bias resistors



Characteristics

- Working point of a detector is define by the Signal to Noise (S/N) ratio of a detector
 - The most probable value of the landau fit to the distribution is defined as the Signal (S)
 - Noise is the fluctuation of charge in absence of signal
 - Mean of the Gaussian distribution



➡ Signal/Noise (S/N) defines working point of the detector

Spatial Resolution

t=1

t=2

- Physical process:
 - Fluctuation in energy loss
 - Diffusion of charge $(r \propto \sqrt{Dt})[*]$
- External parameters
 - Strip pitch
 - Electronic noise
 - Charge sharing with neighbouring strips
 - 100-200 μ n pitch : σ = 10-20 μ m
 - 25 μ m pitch : σ = 2-3 μ m

(*) r = radius of charge cloud

- D = diffusion constant
- t = elapsed time



t=4

Effect of Harsh Radiation Environment

- Secondaries from p-p interaction and their products
- Back scattered neutrons from calorimeter produce
 - Irreversible damage in silicon
 - Increase in leakage current
 - Increase in depletion voltage
 - Deterioration of spatial resolution
- Recovery through annealing not enough
 - Short term beneficial annealing
 - Long term reverse annealing (changes Depletion Voltage)

Substantially degrades performance affecting both aspects : charge collection and spatial resolution

Radiation Damage in Silicon

- Surface damage
 - Decrease in interstrip isolation
- Possible increase in interstrip After Heavy Irradiation **Before Irradiation** capacitance (Type Inversion) p+ strip Signal Spread and Higher Noise p+ strip Bulk damage p-bulk n-bulk Increase in leakage current n+ implant n+ implant • $\Delta J_{\mu} = \alpha \phi$ Depletion p+ strip p+ strip Decrease in charge collection Ballistic deficit n-bulk p-bulk Change in doping concentration n+ implant n+ implant Vbias<Vd Vbias<Vd
 - Type inversion

Radiation Resistant Silicon

- Radiation hardness of silicon sensor depends on
 - Initial dopant concentration, resistivity
 - Crystal orientation
 - Processing purity/quality

It required years of R&D in collaboration with silicon industry

- Low temperature operation (-10^oC) to
 - reduce leakage current
 - control reverse annealing
 - improve charge collection
- High Voltage Operation for
 - effective charge collection

to finally develop radiation hard silicon sensors that can work efficiently for ~ 10 years in extreme LHC conditions

Detector Design Optimization

- Physics performance
- Experiment specific condition
 - Track density, affecting occupancy
 - Occupancy (# of fired strips)
 - Number of strips
 - Pitch (separation)
 - Number of readout channel
 - Trigger rate, available time for signal processing
 - Data size
- Best available industrial facilities
- Mechanical constraint considering overall detector design
- Efficient cooling
- As light as possible for efficient tracking
- Finally, the cost !!



Pixel Detectors (I)

Trcking/vertexing is needed to extend a close as possible to the interaction point

- In very dense environment like LHC, strip detectors are not suitable for this purpose
 - Instead of strips, rectangular pixels used
- Highly segmented detectors
 - Greatly helps in pattern recognition
 - Provides true (3D) high resolution space points
- Readout chips integrated directly on the sensor by bump bonding
 - The pixel size is influenced by the area needed by frond-end chip





Pixel Detector(II)

- Design consideration
 - Distance of the layers from the interaction region
 - Hit Resolution
 - Material budget
 - Extremely high power density requires efficient cooling
 - Radiation environment
 - Size of the signal charge
 - Incident angle of tracks

The Generic Tracking Detector

- Overall detector geometry very much experiment specific
 - But almost in all cases :
 - a few layers of pixel detectors used close to the interaction point
 - Followed by layers of Strip detectors

Pixel : Vertex, IP, angle

Strip: Momentum (range depends on the length of the tracker)

Hit Reconstruction

- Charged Particle traversal through silicon sensor
 - Charge Collection
 - measure S/N
 - particle identification (dE/dx)
 - Hit position
 - 3-threshold Clustering algorithm
 - weighted average of strip position and corresponding charges
- Once hits are found in different layers of the tracker we can proceed with the track reconstruction



Track Reconstruction

- Define an initial track segment using a few hits (seed)
- Follow a track candidate picking up hits iteratively
- Use track model to extrapolated to the next layer
- Consider material to be traversed to define search and measurement error
 - Multiple scattering
 - Θ_{MS} = 0.9 mrad in 300 µm silicon
- Include hits inside the search window
 - If more hits, create separate branches
- Consider detector inefficiencies
 - If no hits found, in a layer, move to at least next layer
 - All known efficiencies should be considered
 - Track candidate missing hits in several layers do not consider the





Track Reconstruction



Vertex Reconstruction (I)

Classification of reconstructed tracks in an event such that all tracks associated with a candidate originate at the vertex

- In collider and fixed target experiments interaction vertex is called "primary vertex"
- If particles are created due to decay of unstable particles, the decay vertex is called "secondary vertex"
- If the particles are produced due to interaction with detector material, it is "secondary interaction vertex"
- Different techniques and algorithms used to reconstruct vertices
 - Primary vertex finding relatively easier than secondary vertex finding

Vertex Reconstruction (II)

- Primary vertex
 - Very high multiplicity
 - Needed as reference many other reconstruction steps apriori
- Secondary vertex
 - Needed for reconstruction of long lived particle
 - Low multiplicity
 - Track association and vertex separation is a challenging





Steps in Primary Vertex finding (III)

- Find approximate vertex position first
 - Crossing point for each track pair
 - Define weight of each track proportoinal to the distance of the tracks
 - Mode of crossing points
- Weight tracks according to their standardized distance wrt vertex
- Apply specified algorithms to clean the vertex removing non compatible tracks
- Discarded tracks re-clustered to find new vertex
- Iterate over last three steps
- Stop the procedure when distance between different vertexes are smaller than a predefined value after N iterations